Special Issue

Nano/Microscale Thin-Film Photocathodes: Materials and Applications

Message from the Guest Editor

Thin-film photocathodes in typical nano/microscale form are prevalently utilized to provide electron beams of increasingly stringent requirements for interdisciplinary researches and practical applications. The design capabilities of photocathodes in electron sources/devices have become an enabling technology in diverse fields such as light sources and detectors, electron cooling, ultrafast electron diffraction, novel particle accelerators, radiology and radiation oncology, electron beam lithography, etc. This Special Issue (SI) aims to summarize recent advances in nano/microscale thin-film photocathode materials across (but not limited to) the above-stated application fields with a focus on cathode materials and performances for light sources and detectors, novel particle accelerators, and ultrafast electron diffraction.

Guest Editor

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